FIG. 1

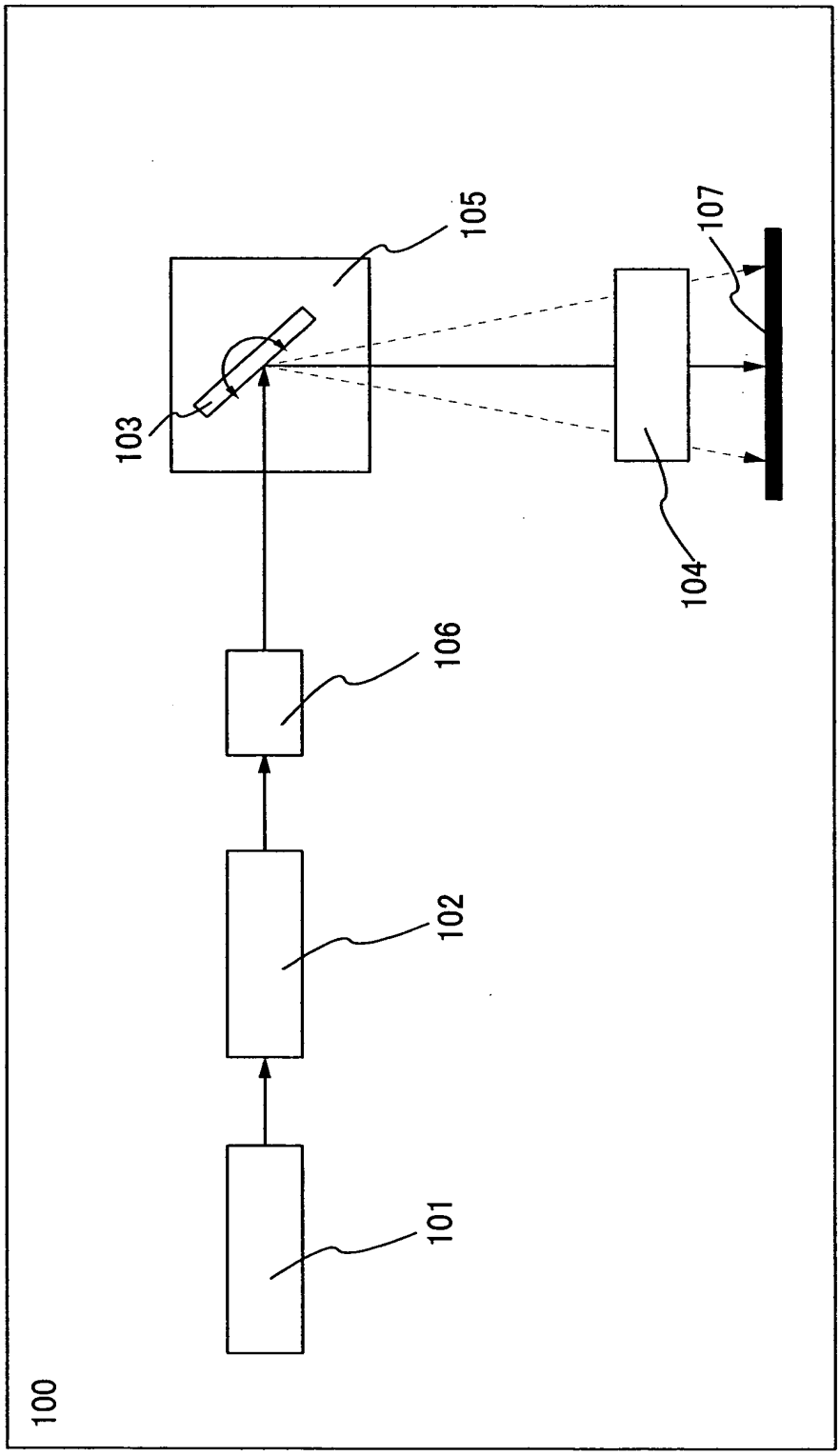

FIG. 2

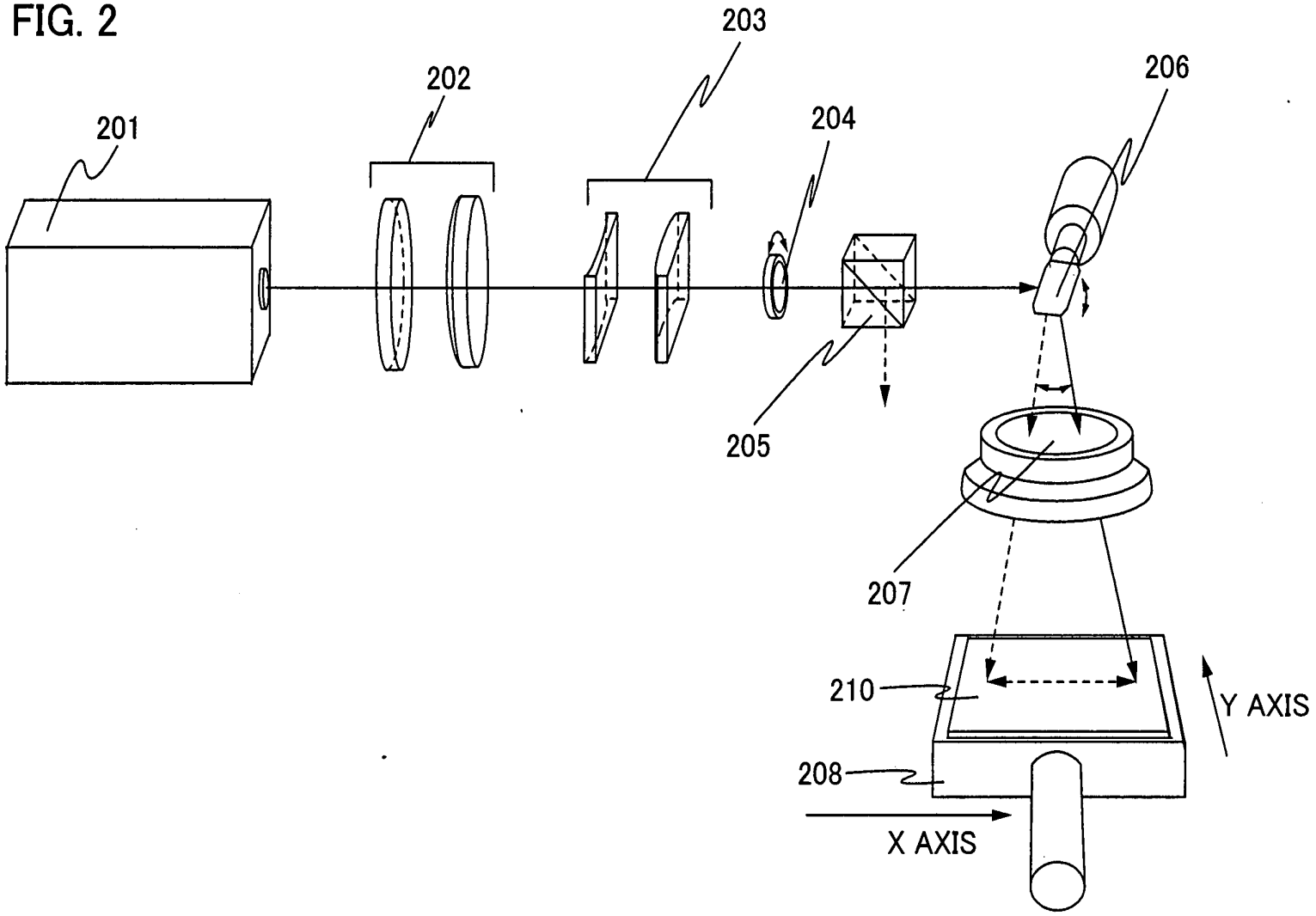

FIG. 3A

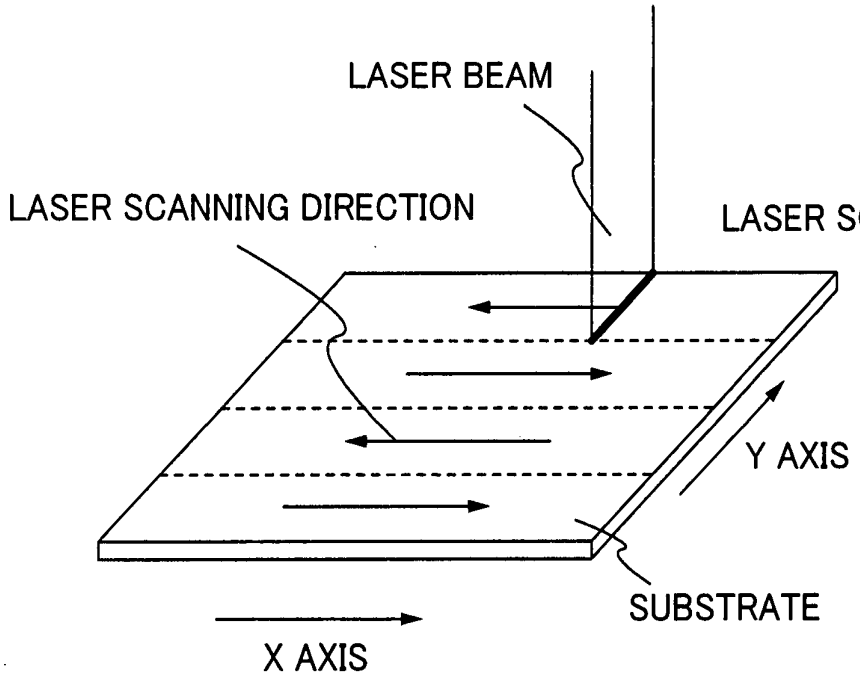
LASER BEAM
LASER SCANNING DIRECTION
Y AXIS
SUBSTRATE
X AXIS

FIG. 3B

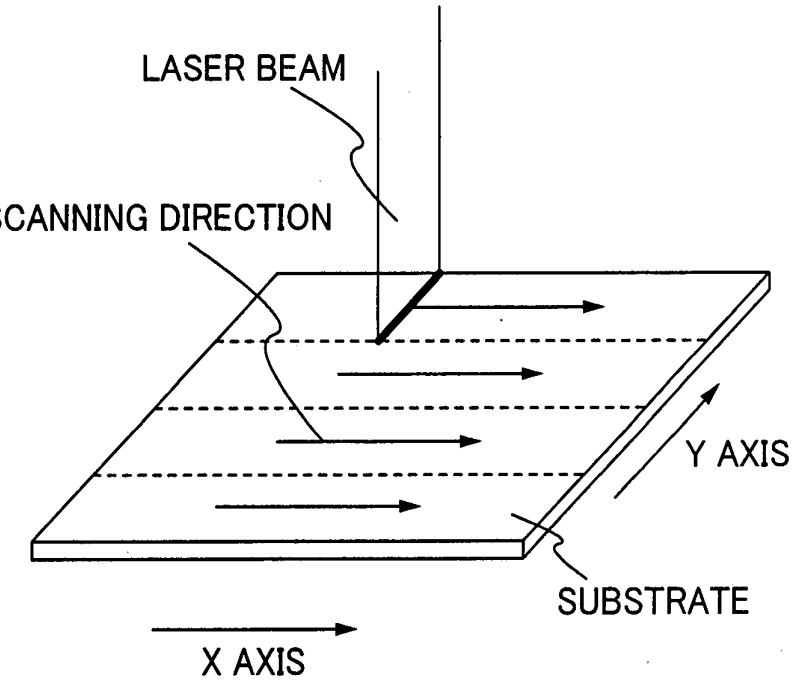
LASER BEAM
LASER SCANNING DIRECTION
Y AXIS
SUBSTRATE
X AXIS

FIG. 4A

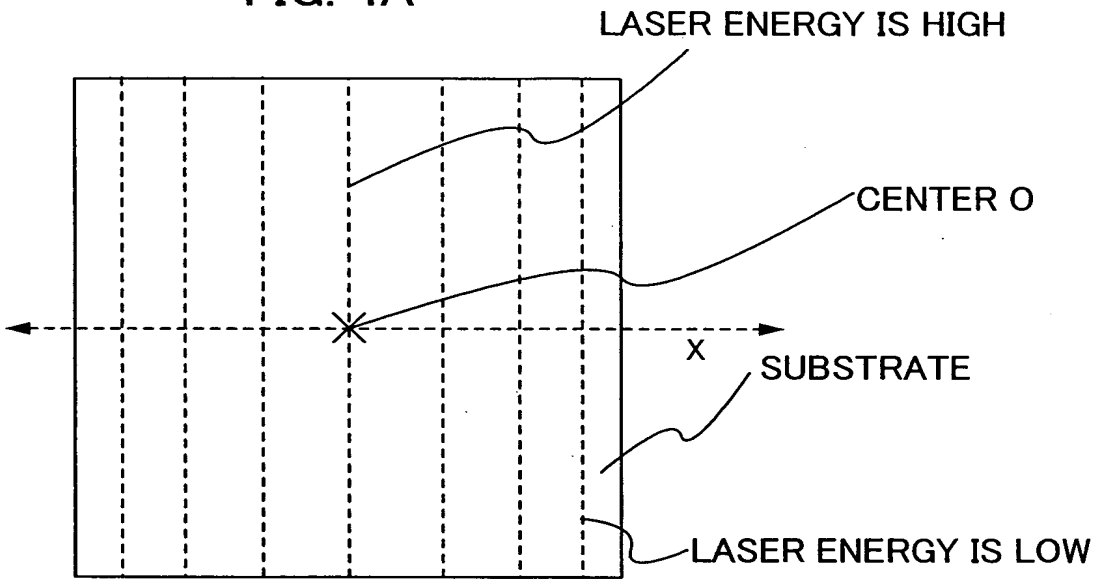
LASER ENERGY IS HIGH
CENTER O
X
SUBSTRATE
LASER ENERGY IS LOW

FIG. 4B

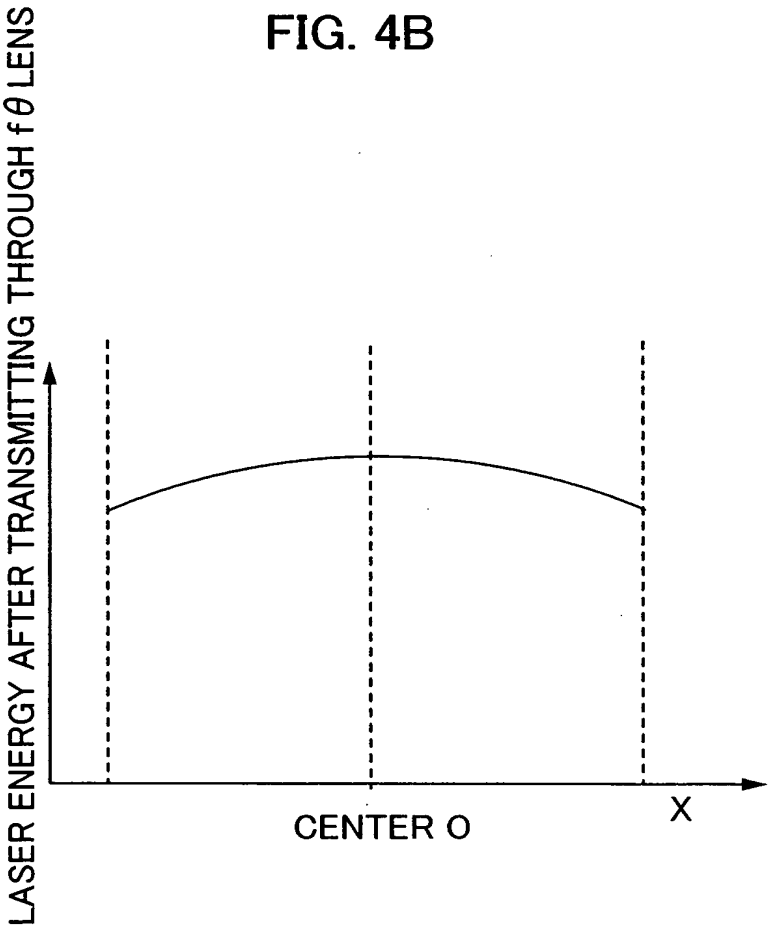
LASER ENERGY AFTER TRANSMITTING THROUGH fθ LENS
CENTER O
X

FIG. 5A

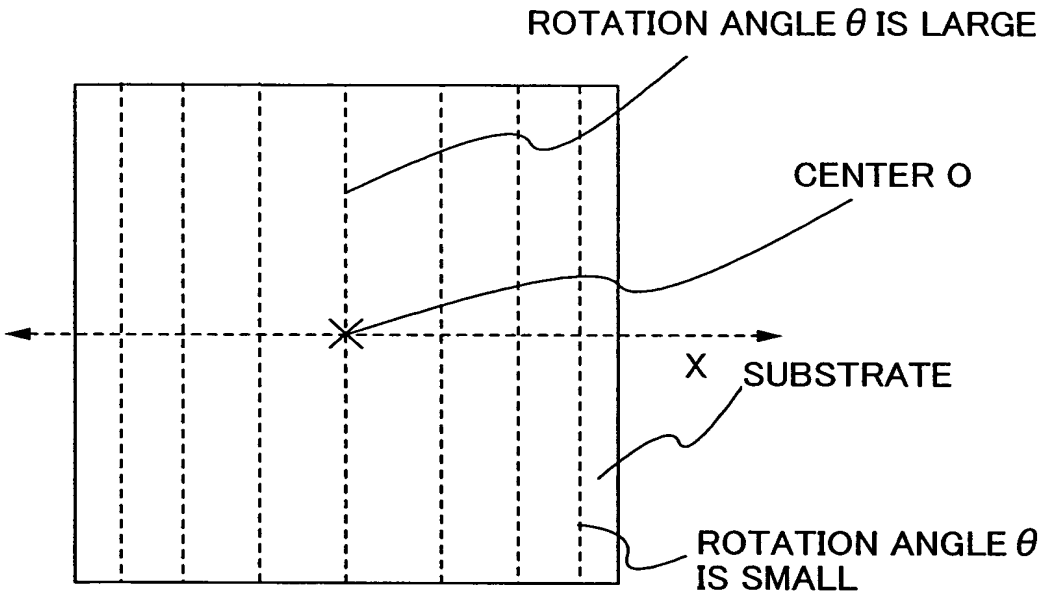
ROTATION ANGLE θ IS LARGE
CENTER O
X
SUBSTRATE
ROTATION ANGLE θ
IS SMALL

FIG. 5B

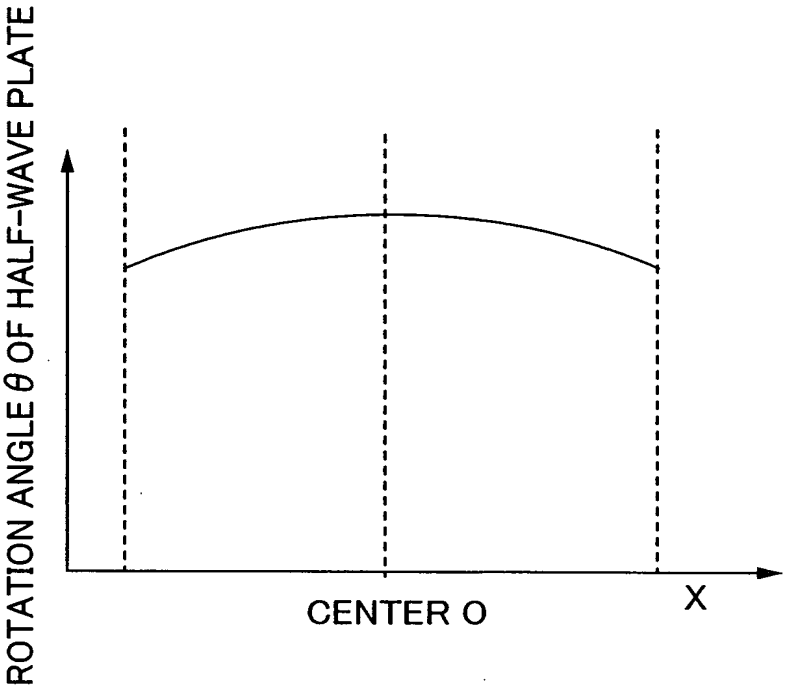
ROTATION ANGLE θ OF HALF-WAVE PLATE
CENTER O
X

FIG. 6A

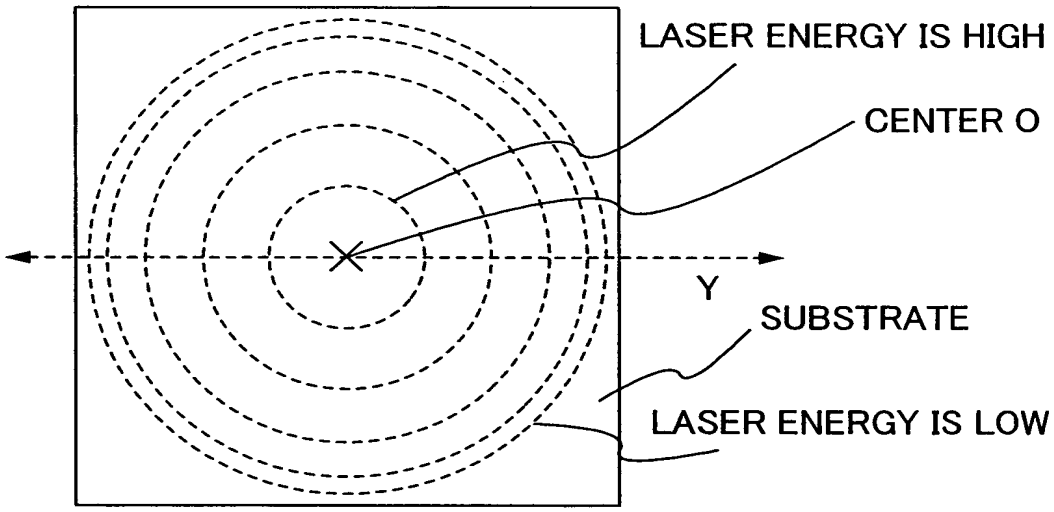
LASER ENERGY IS HIGH
CENTER O
Y
SUBSTRATE
LASER ENERGY IS LOW

FIG. 6B

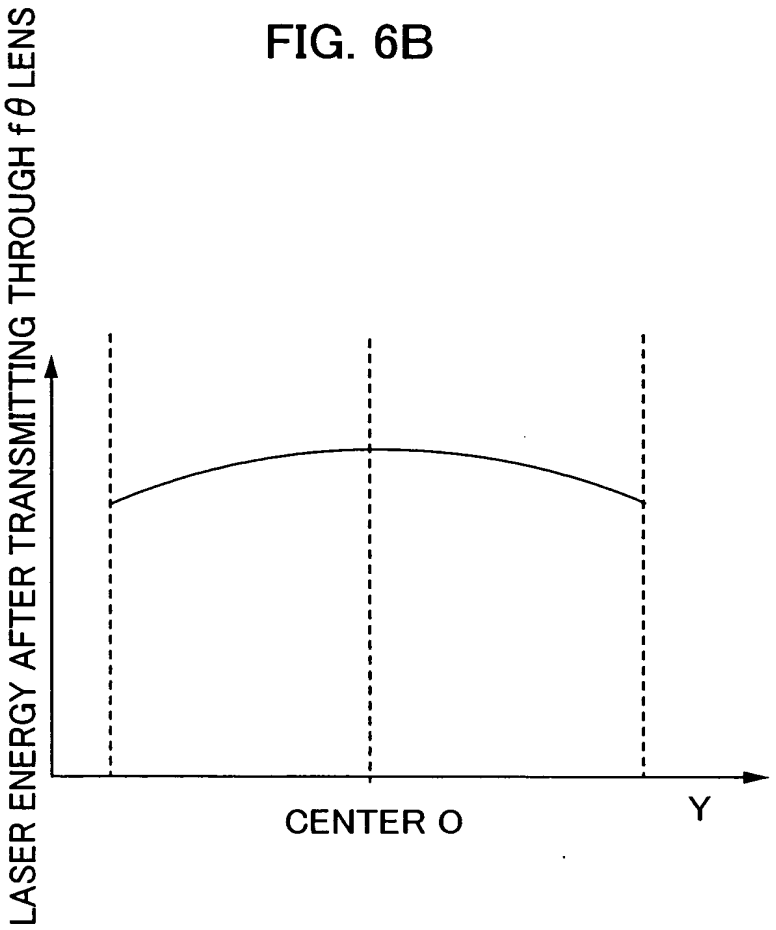
LASER ENERGY AFTER TRANSMITTING THROUGH fθ LENS
CENTER O
Y

FIG. 7A

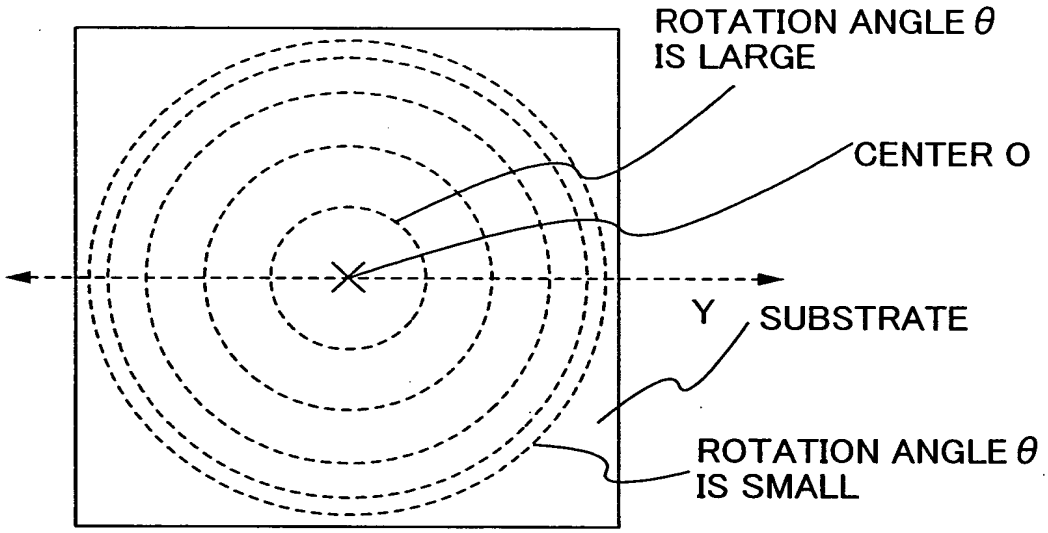
ROTATION ANGLE θ
IS LARGE
CENTER O
Y
SUBSTRATE
ROTATION ANGLE θ
IS SMALL

FIG. 7B

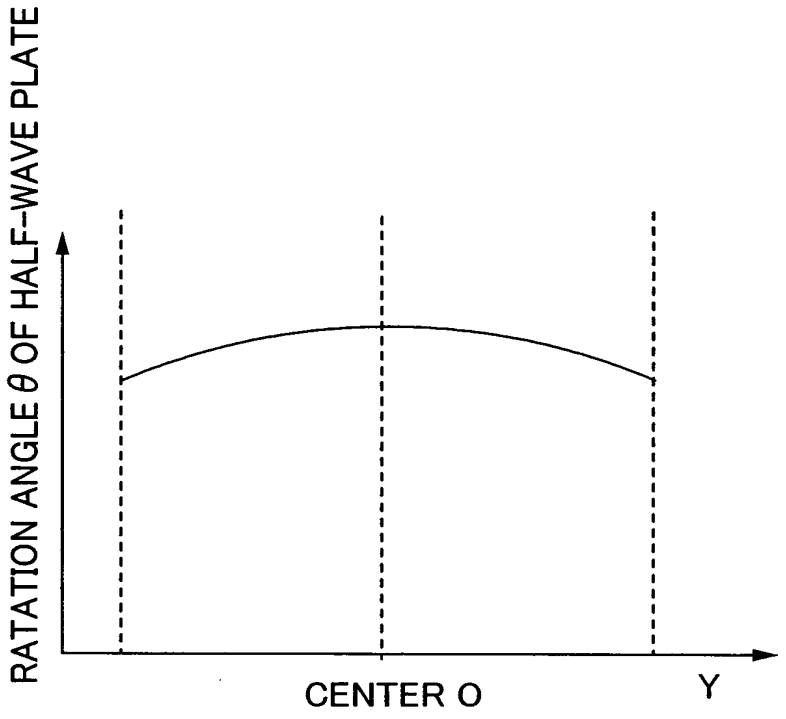
RATATION ANGLE θ OF HALF-WAVE PLATE
CENTER O
Y

FIG. 8A

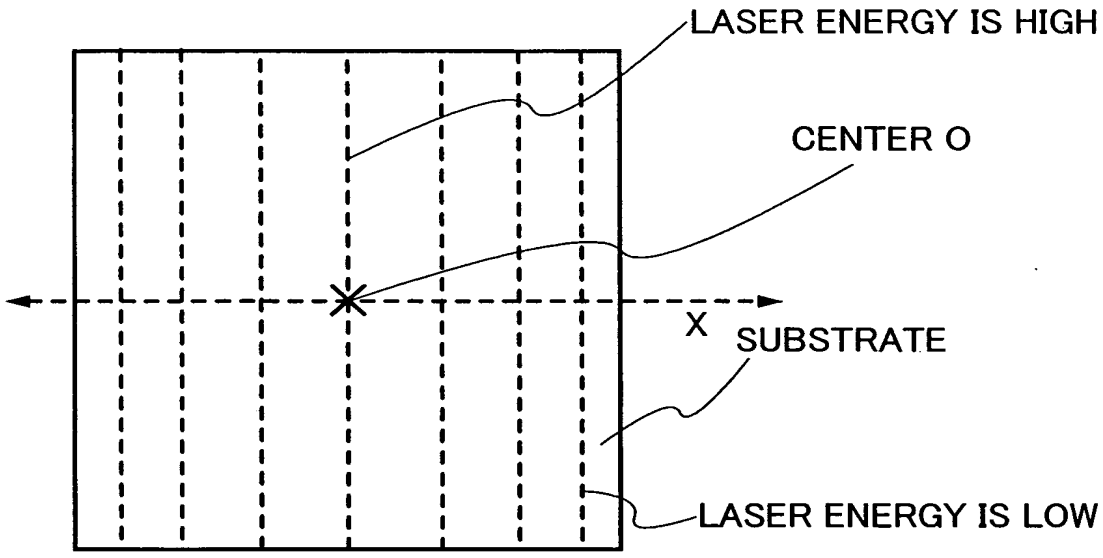
LASER ENERGY IS HIGH
CENTER O
X
SUBSTRATE
LASER ENERGY IS LOW

FIG. 8B

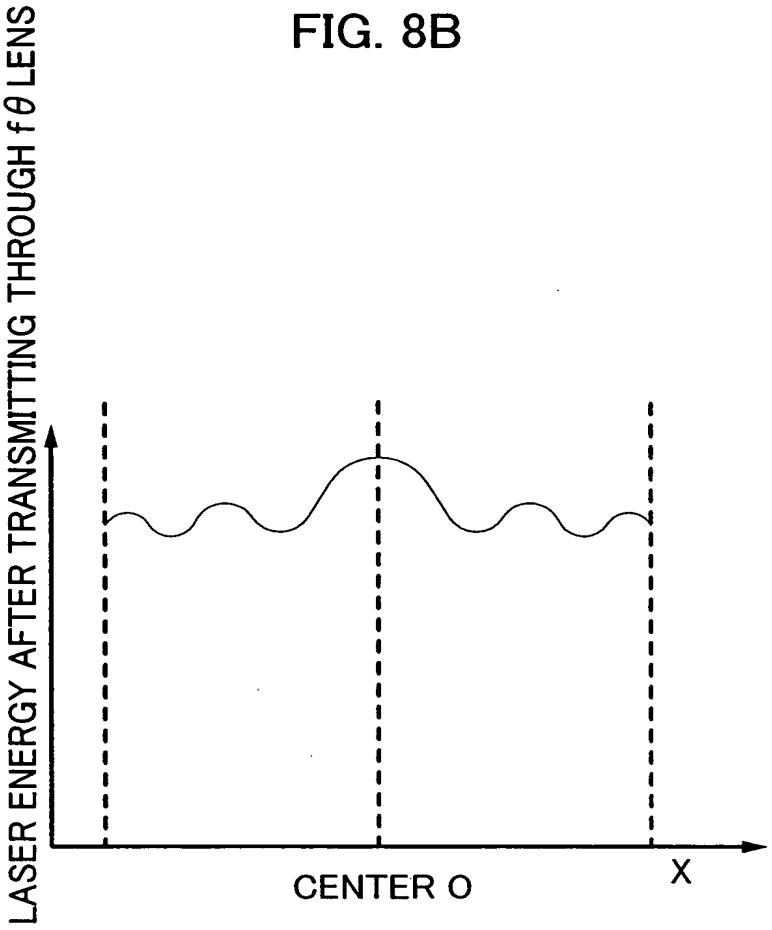
LASER ENERGY AFTER TRANSMITTING THROUGH fθ LENS
CENTER O
X

FIG. 9

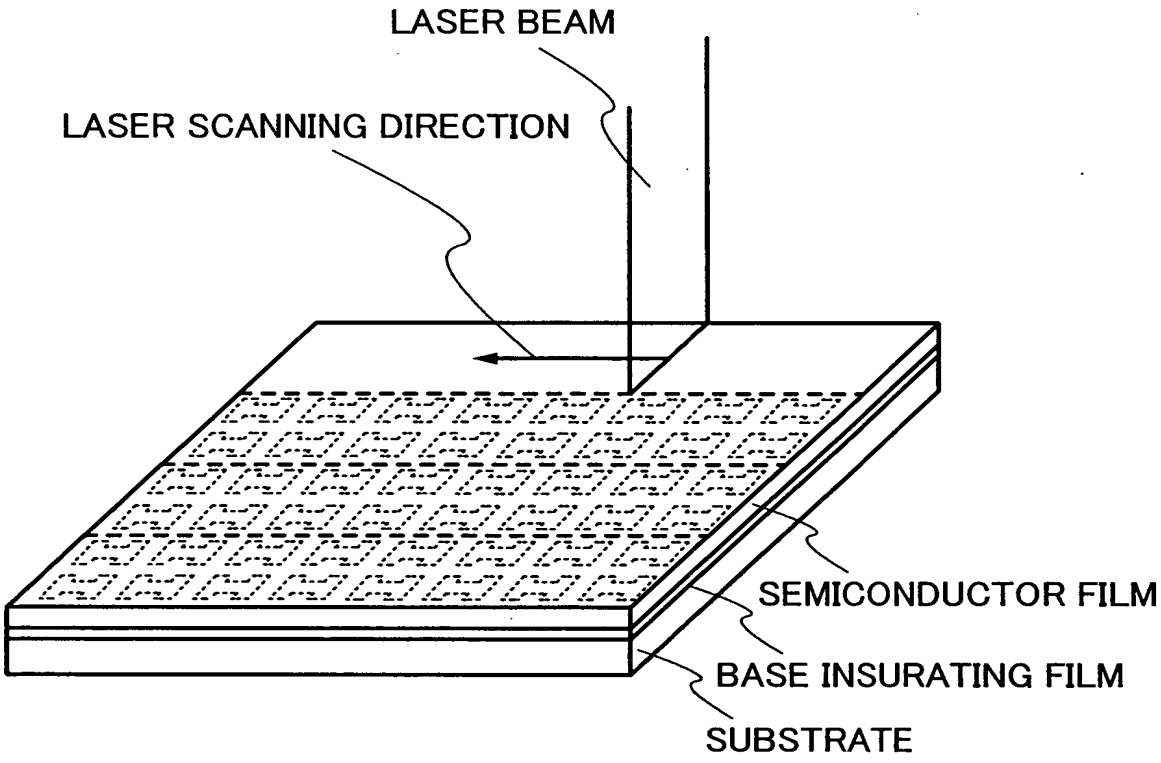
LASER BEAM
LASER SCANNING DIRECTION
SEMICONDUCTOR FILM
BASE INSURATING FILM
SUBSTRATE

FIG. 10A

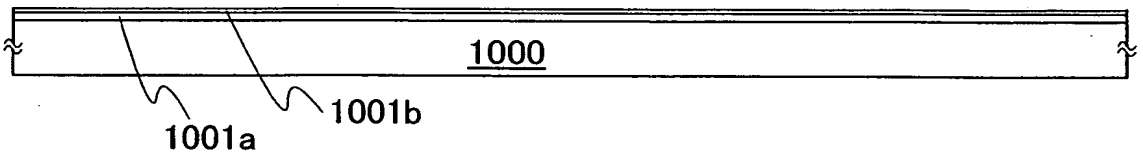

FIG. 10B

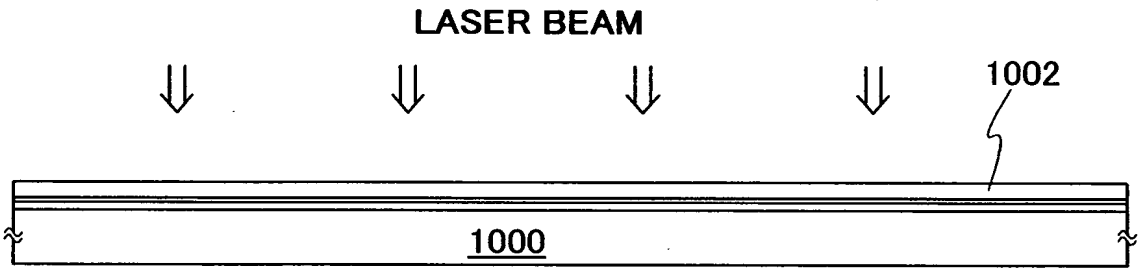

FIG. 10C

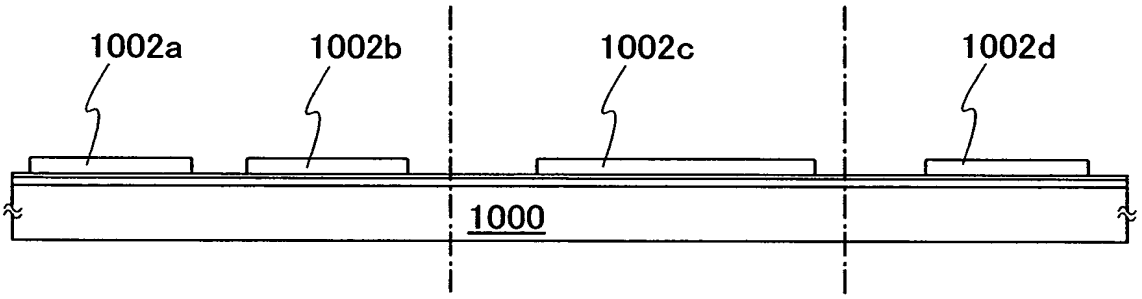

FIG. 10D

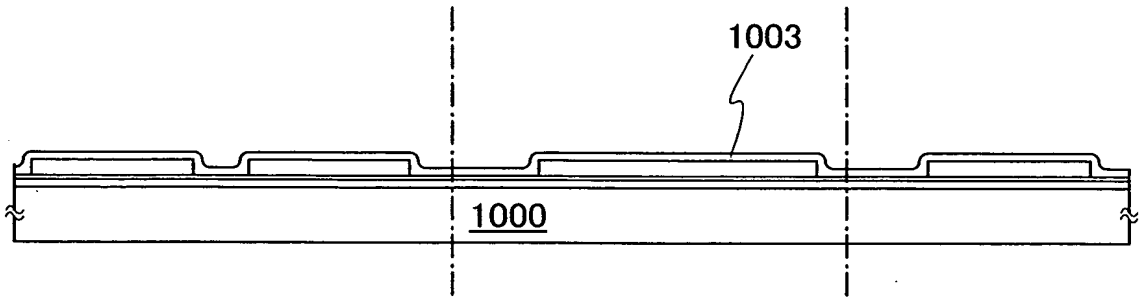

FIG. 11A

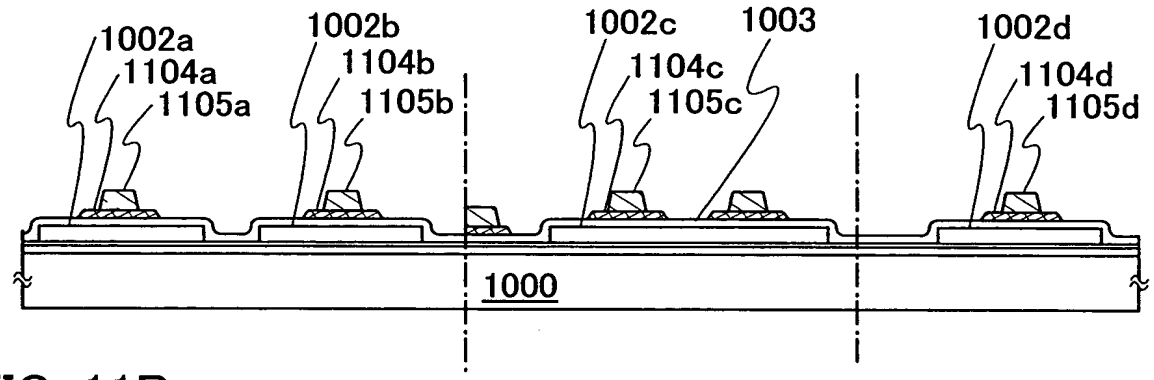

FIG. 11B

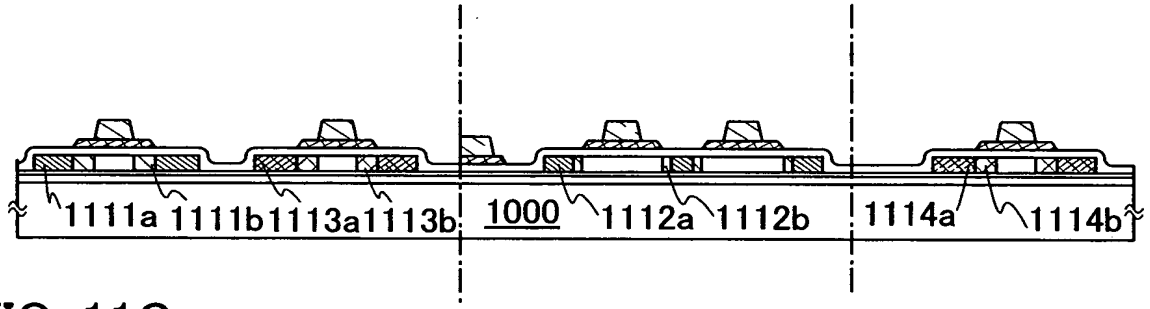

FIG. 11C

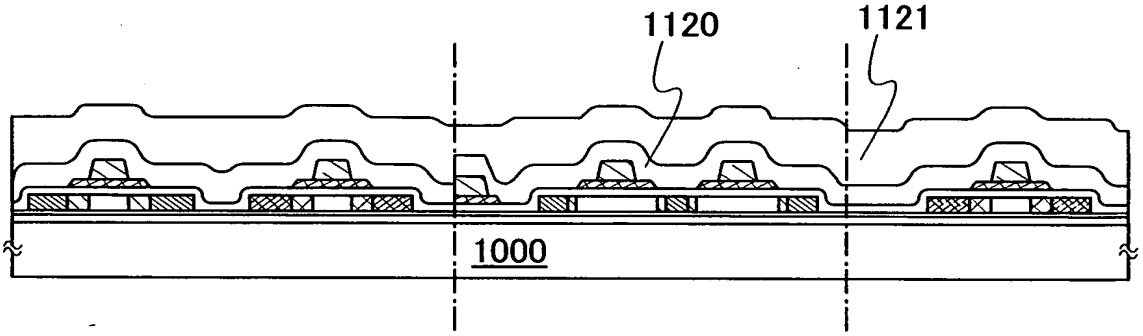
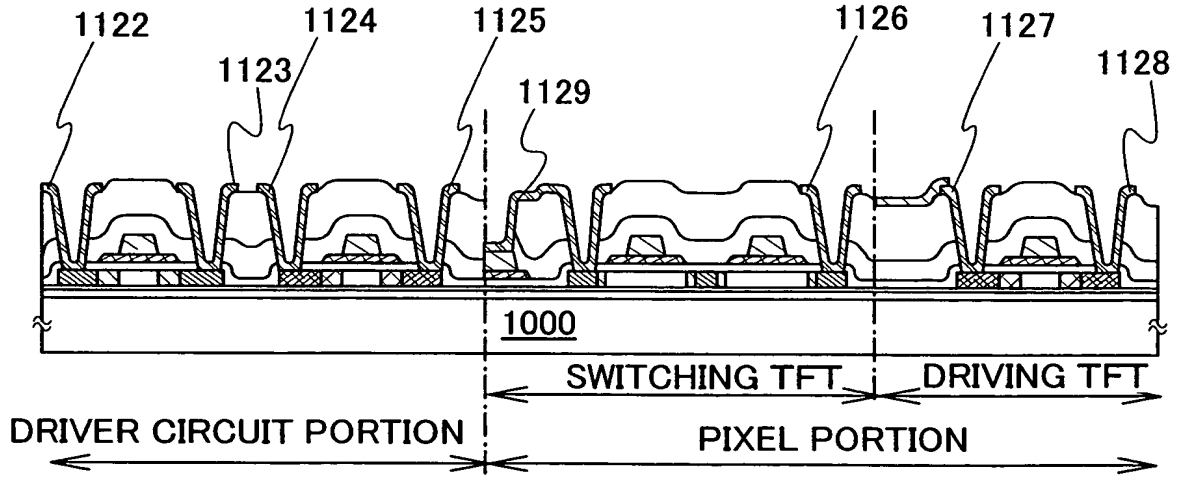
FIG. 11D